



U.S. Department of Commerce, Patent and Trademark INFORMATION DISCLOSURE STATEMENT BY APPLICANT	Atty. Docket No.	Application No.
	TNCR.189US0	09/741,663
(Use several sheets if necessary)	Applicant(s)	Conf. No.
	Andrei V. Shchegrov	7526
	Filing Date	Group
	December 19, 2000	2877

## U.S. Patent Documents

*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate

## Foreign Patent Documents

							Translation	
	Document	Date	Country	Class	Subclass		Yes	No

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	1	Patent Search conducted on August 1, 2000
	2	"Ultraviolet-visible ellipsometry for process control during the etching of submicrometer features," N. Blayo et al., <i>J. Opt. Soc. Am. A</i> , Vol. 12, No. 3, March 1995, pp. 591-599.
	3	"Algorithm Implementation and Techniques for Providing More Reliable Overlay Measurements and Better Tracking of the Shallow Trench Isolation (STI) Process," D. Schramm et al., <i>SPIE: Conference on Metrology, Inspection, and Process Control of Microlithography XIII</i> , March 1999, pp. 116-122.

Examiner	Date Considered 27 August 2004
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.